CENTRAL FAX CENTER

AUG 0 1 2007

Form 1449 (Modified)	Atty Docket No.	Application No.:
Information Disclosure Statement By Applicant	NOVLP068/NVLS-2818 Applicant: Koos et al.	10/690,084
(Use Several Sheets if Necessary)	Filing Date October 20, 2003	Group : 1765

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Examiner	<u>.</u>	/Lan Vinh/	Date Considered 09/28/2007

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Applicant:
Statement By Applicant

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Filing Date Group

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U.S. Patent and Publication Documents

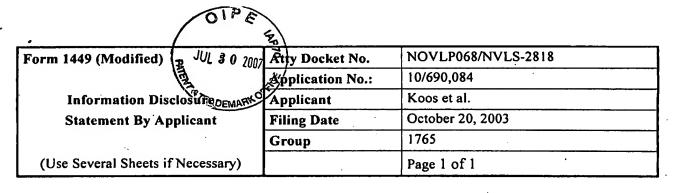
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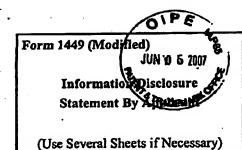
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Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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